

**AMENDMENTS TO THE SPECIFICATION**

**Please delete the present Abstract of the Disclosure.**

**Please add the following new Abstract of the Disclosure:**

A method of forming a metal oxide film by the plasma CVD method and which  
includes~~comprising~~ reacting chiefly an organometal by a glow discharge in a low output region  
and, then, reacting the organometal with an oxidizing gas by the glow discharge in a high-output  
region to form a metal oxide film on the surface of a plastic substrate via an organic layer. This  
method forms a thin film having excellent adhesiveness, softness and flexibility on the surface of  
a plastic substrate relying on the plasma CVD method.